



# PRESIDENCY UNIVERSITY

BENGALURU

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## Make up Examinations – December 2025

Date: 31 – 12- 2025

Time: 09:30am – 12:30pm

School: SOE	Program: B Tech-VLSI	
Course Code : ECE2012	Course Name : Solid State Electronics	
Semester: MK	Max Marks: 100	Weightage: 50%

CO - Levels	CO1	CO2	CO3	CO4	CO5
Marks	10	10	20	30	30

### Instructions:

- (i) Read all questions carefully and answer accordingly.  
(ii) Do not write anything on the question paper other than roll number.

### Part A

Answer ALL the Questions. Each question carries 2marks.

10Q x 2M=20M

1	Identify the quantum mechanical phenomenon in which an object such as an electron or atom passes through a potential energy barrier that, according to classical mechanics, should not be passable due to the object not having sufficient energy to pass or surmount the barrier.	2 Marks	L1	CO2
2	The way the atoms are bonded, in a NaCl is different from that of a Carbon. Name the type of bonding in NaCl and Carbon.	2 Marks	L1	CO2
3	In any material, the Pauli's exclusion principle plays an important role in bandgap formation. State Pauli's exclusion principle.	2 Marks	L1	CO2
4	John observed that if same electric field is applied to an electron in vacuum and in a crystal, it accelerates with different velocities. Why?	2 Marks	L1	CO2
5	At thermal equilibrium, the electron and hole concentration relationship is given by the mass action law. Write mathematically the expression for the mass action law.	2 Marks	L1	CO2

6	A Field Effect Transistor is a unipolar transistor with three terminals. Name the three terminals of a JFET.	2 Marks	L1	C05
7	Billions of MOS transistors are used, together in semiconductor memory devices and microprocessors. List any two features of Field Effect Transistor that enable them for above application.	2 Marks	L1	C05
8	In any FETs, the width of the channel can be controlled, by applying a voltage to the gate, which in turn controls the current flowing from the source to the drain. Identify the gate voltage at which the drain current reaches the saturation value.	2 Marks	L1	C05
9	Shorter channels experience a reduction in the effective channel length as $V_{DS}$ increases, leading to a rise in $I_D$ even in saturation. Write the equation for the modified saturation current for a short channel MOSFET.	2 Marks	L1	C05
10	2DEG(2 Dimensional Electron Gas) is formed at the interface of the materials due to differences in their band gaps. This 2DEG acts as a high-mobility electron channel for current flow. In which type of transistor 2DEG is commonly seen?	2 Marks	L1	C05

### Part B

#### Answer the Questions

Total 80 Marks

11.	a.	LEDs use direct band semiconductors whereas for the making of transistors, indirect band semiconductors are used. Is the above statement true? Explain with necessary diagrams the various types of semiconductors based on band gap.	10 Marks	L2	C01
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Or

12.	a.	In solids, the formation of a bandgap is directly linked to the Pauli exclusion principle. Explain the formation of bandgap in Carbon with the help of a neat diagram.	10 Marks	L2	C01
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13.	a.	Zener breakdown typically occurs at lower voltages (around 5 volts or less), while avalanche breakdown happens at higher voltages exceeding that range; meaning the voltage above which both breakdown types occur is considered to be around 5 volts and higher where the avalanche effect becomes dominant. Explain the breakdown processes in a p-n junction diode with necessary diagrams.	10 Marks	L2	C03
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Or

14.	a.	Consider a Silicon pn junction at room temperature doped at $N_a=10^{16}/\text{cm}^3$ in the p region and $N_d=10^{17}/\text{cm}^3$ in the n region. Intrinsic carrier density is $1.5 \times 10^{10}/\text{cm}^3$ at room temperature. Find the barrier potential and width of the depletion region. For Si the permittivity is given as $1.04 \times 10^{-12}$ F/cm, Charge of an electron $1.6 \times 10^{-19}$ C.	10 Marks	L2	C03
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15.	a.	According to Quantum mechanics, there is a finite probability that carriers can penetrate through the barrier of thin width. Explain the diode working on above phenomenon.	10 Marks	L2	C03
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**Or**

16.	a.	A metal-semiconductor junction is formed when a metal comes into contact with a semiconductor material. Explain the various types with necessary diagrams.	10 Marks	L2	C03
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17.	a.	Unlike conventional Bipolar Junction Transistors (BJTs), HBTs use different semiconductor materials for the emitter and base regions, which gives them unique advantages. Explain about Heterojunction Bipolar transistors.	15 Marks	L2	C04
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**Or**

18.	a.	A transistor is an important solid state electronic device used in amplification and switching applications. Explain the operation of BJT with the help of p-n-p transistor and derive the amplification factor $\beta$ .	15 Marks	L2	C04
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19.	a.	The Early effect is a phenomenon that occurs in bipolar junction transistors (BJTs) when the effective width of the base changes due to a variation in the base-to-collector voltage. Discuss how the base width variation affects the normal working of a BJT.	15 Marks	L2	C04
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**Or**

20.	a.	The current gain of a BJT decreases at high collector current. Is the above statement true? Justify your answer with necessary explanations and diagrams.	15 Marks	L2	C04
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21.	a.	Metal Oxide Semiconductor Field Effect Transistors are voltage-controlled devices, in which a metal electrode placed on top of an insulator (typically SiO <sub>2</sub> ) on the silicon surface, is used to control the flow of current between two ohmic contacts on the silicon. Explain the working of MOSFET with necessary diagrams and equations.	20 Marks	L2	C05
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**Or**

<b>22.</b>	<b>a.</b>	CMOS is based on metal-oxide semiconductor field-effect transistor (MOSFET) technology, which uses switches or amplifiers to control the amount of electricity flowing between terminals. Explain the various processes involved in CMOS fabrication with necessary diagrams and the working of a CMOS technology based inverter.	<b>20 Marks</b>	<b>L2</b>	<b>C05</b>
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**\*\*\*\*\* BEST WISHES \*\*\*\*\***